

Supporting Information (SI)

# Solution Processed Cu<sub>2</sub>S Nanostructures for Solar Hydrogen Production

Xi Zhang<sup>a</sup>, Stephan Pollitt<sup>b</sup>, Gihun Jung<sup>c</sup>, Wenzhe Niu<sup>a</sup>, Pardis Adams<sup>a</sup>, Jan Bühler<sup>a</sup>, Nora S. Grundmann<sup>a</sup>, Rolf Erni<sup>d</sup>, Maarten Nachtegaal<sup>b</sup>, Neul Ha<sup>ef</sup>, Jisu Jung<sup>ef</sup>, Byungha Shin<sup>c</sup>, Wooseok Yang<sup>ae<sup>f</sup>\*</sup>, S. David Tilley<sup>a\*</sup>

<sup>a</sup>*Department of Chemistry, University of Zurich, Winterthurerstrasse 190, 8057 Zurich, Switzerland*

<sup>b</sup>*Paul Scherrer Institut (PSI), Forschungsstrasse 111, 5232 Villigen, Switzerland*

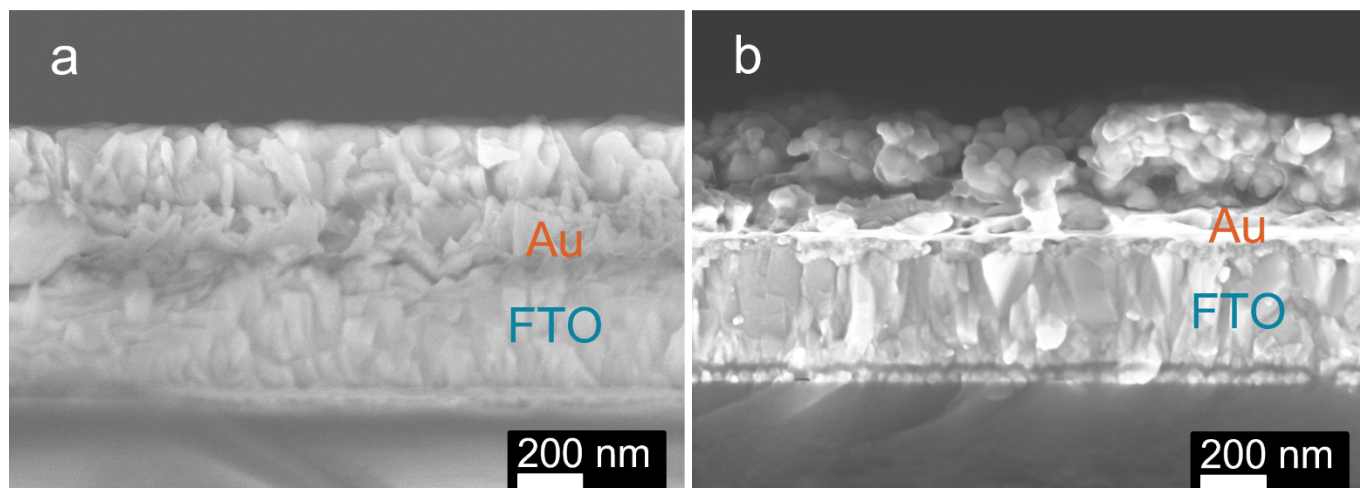
<sup>c</sup>*Department of Materials Science and Engineering, Korea Advanced Institute of Science and Technology (KAIST), 291 Daehak-ro, Yuseong-gu, Daejeon 34141, Republic of Korea*

<sup>d</sup>*Electron Microscopy Center, Empa, Swiss Federal Laboratories for Materials Science and Technology, Überlandstrasse 129, 8600 Dübendorf, Switzerland*

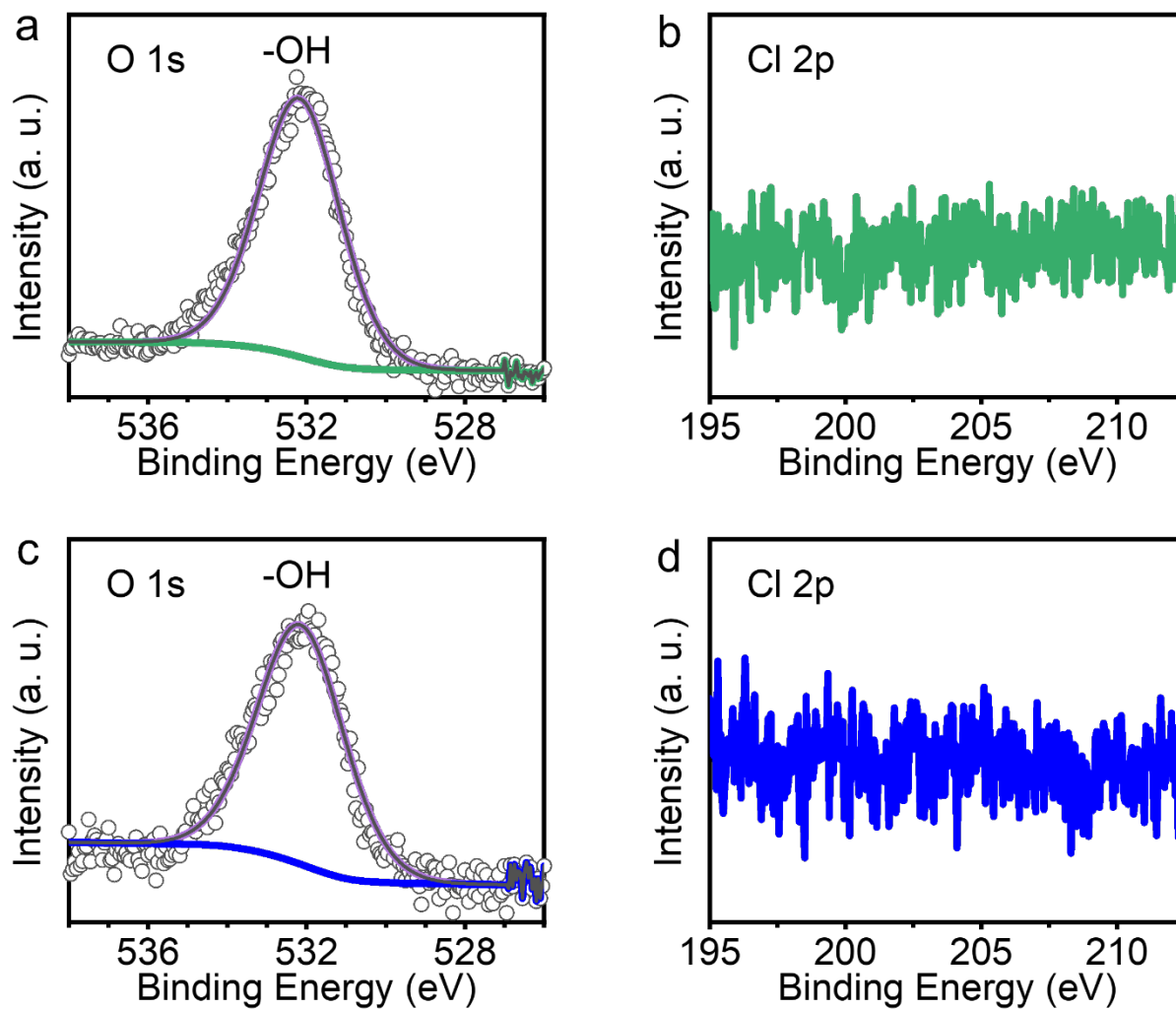
<sup>e</sup>*School of Chemical Engineering, Sungkyunkwan University, 2066 Seobu-ro, Jangan-gu, Suwon-si, Gyeonggi-do 16419, Republic of Korea*

<sup>f</sup>*SKKU Institute of Energy Science and Technology (SIEST), Sungkyunkwan University, Suwon 16419, Republic of Korea*

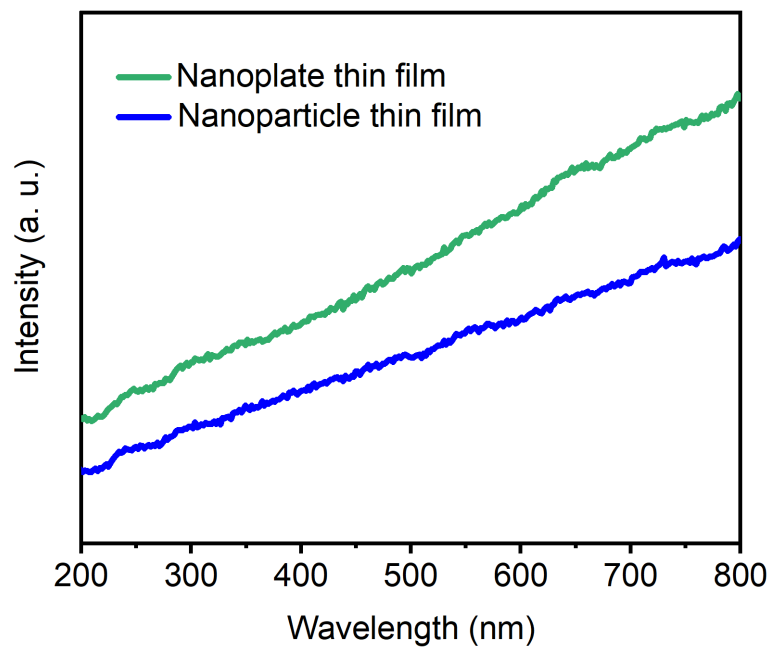
\*Email: [wooseok.yang@skku.edu](mailto:wooseok.yang@skku.edu), [david.tilley@chem.uzh.ch](mailto:david.tilley@chem.uzh.ch)



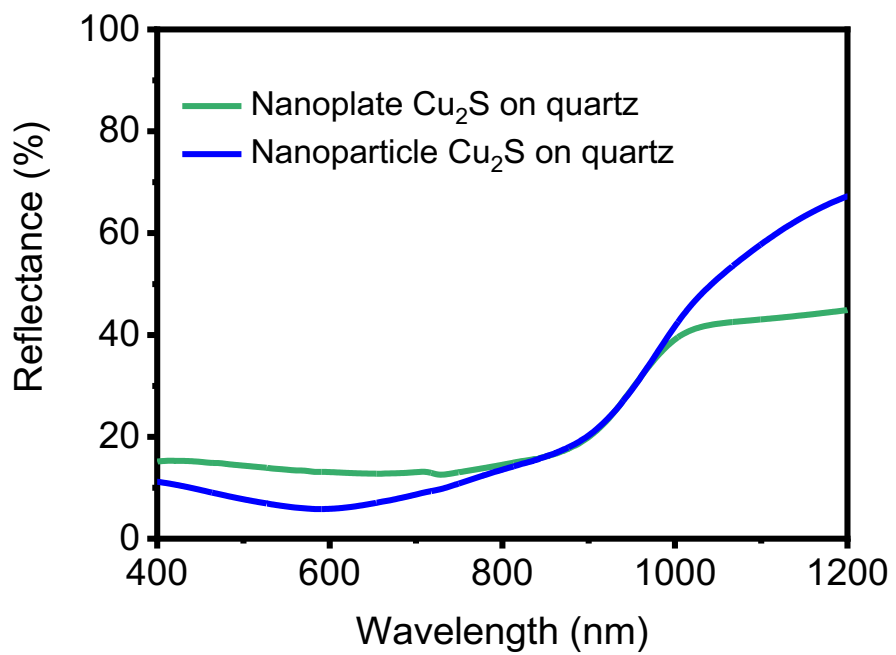
**Figure S1.** Cross-sectional SEM images of thin films prepared from (a) 0.35 M CuCl ink and (b) 0.35 M CuCl<sub>2</sub> ink.



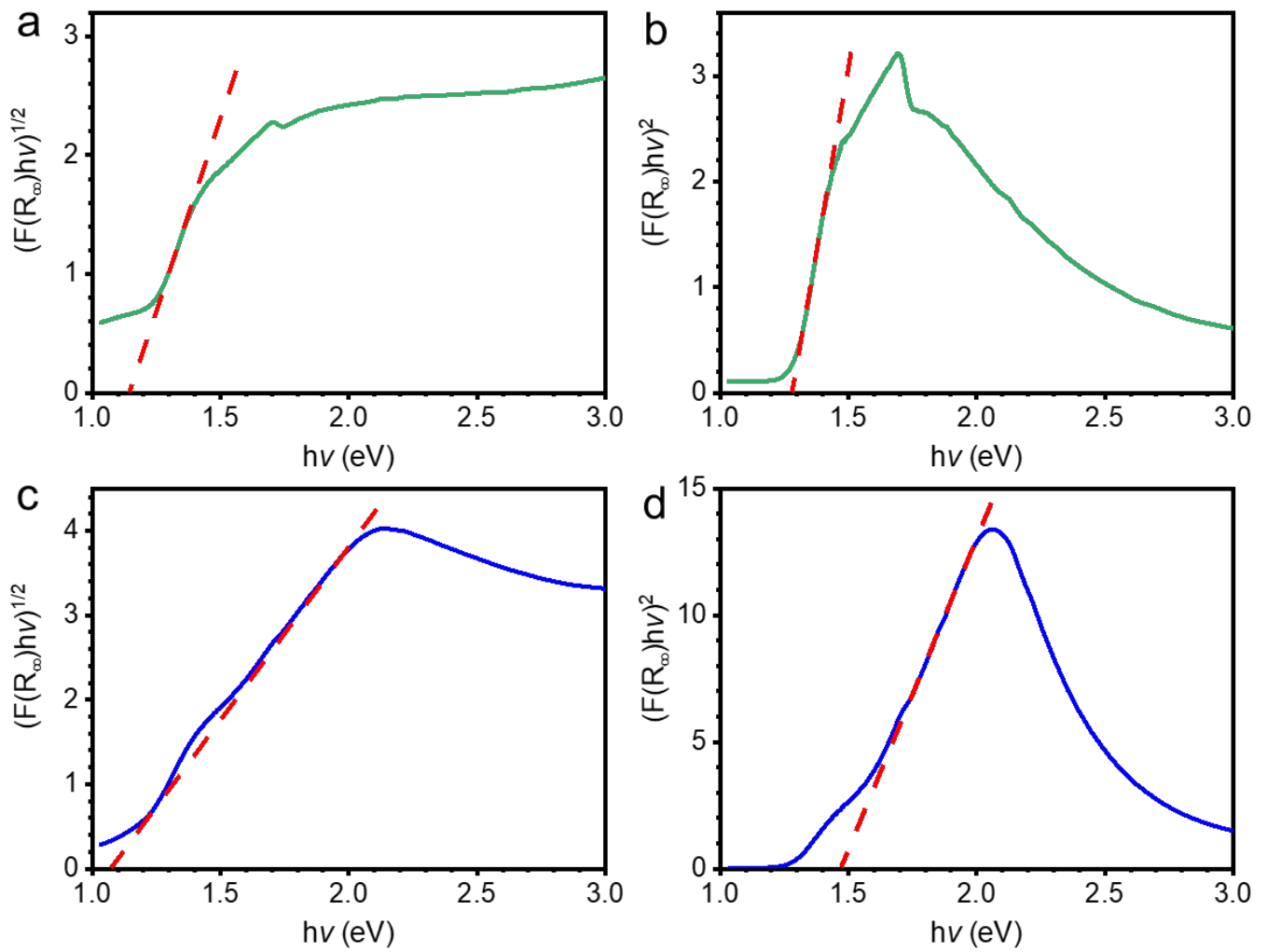
**Figure S2.** (a, c) O 1s XPS spectrum and (b, d) Cl 2p XPS spectrum of (a, b) nanoplate thin film prepared from 0.35 M CuCl ink and (c, d) nanoparticle thin film prepared from 0.35 M CuCl<sub>2</sub> ink.



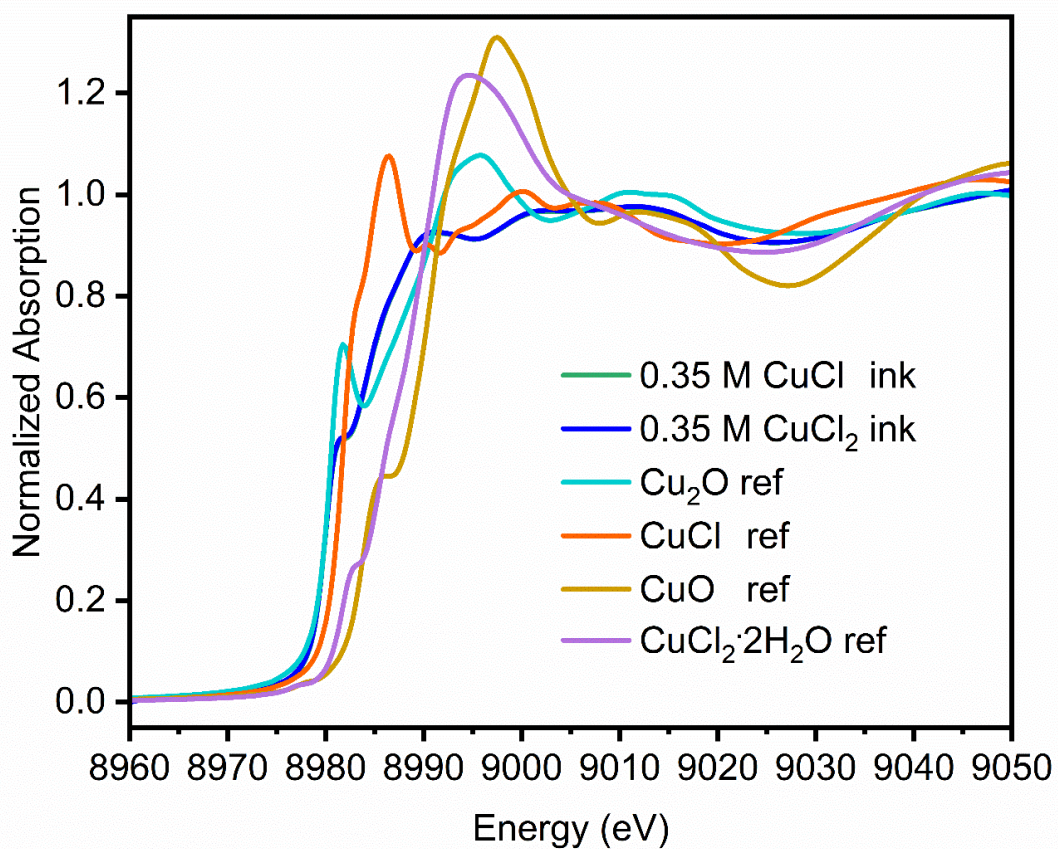
**Figure S3.** Raman spectra of prepared nanoplate and nanoparticle thin films.



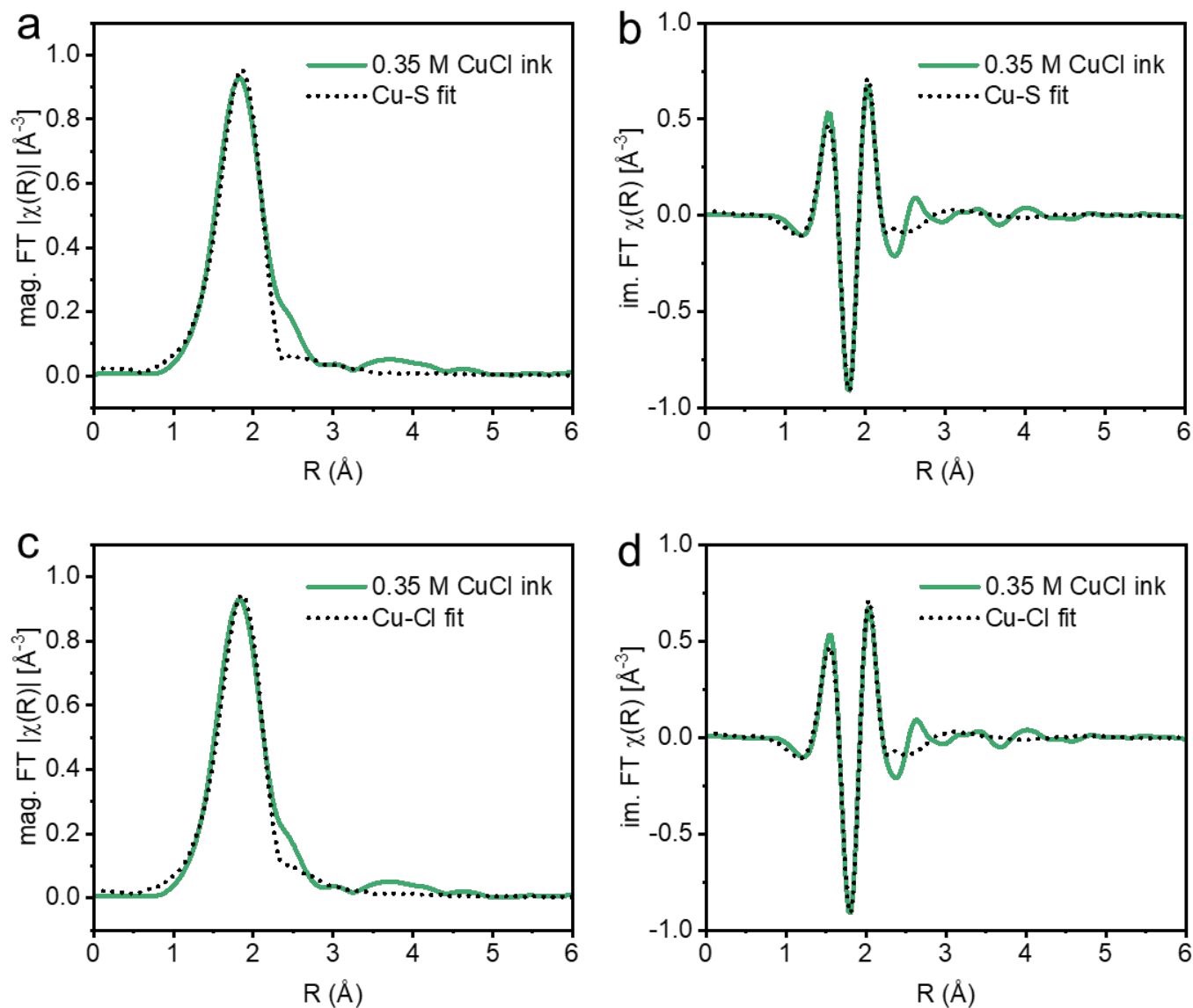
**Figure S4.** The reflectance spectra of nanoplate and nanoparticle  $\text{Cu}_2\text{S}$  thin films on quartz substrates.



**Figure S5.** Tauc plots of nanoplate (a, b) and nanoparticle (c, d)  $\text{Cu}_2\text{S}$  thin films to determine their indirect (a, c) and direct (b, d) band gap energies ( $E_g$ ). The linear parts of the plots are extrapolated to the x-axis.



**Figure S6.** Cu K-edge X-ray absorption near-edge structure (XANES) spectra for 0.35 M CuCl and CuCl<sub>2</sub> molecular inks (which overlap fully) along with pressed Cu<sub>2</sub>O, CuO, CuCl and CuCl<sub>2</sub>·2H<sub>2</sub>O powder references.



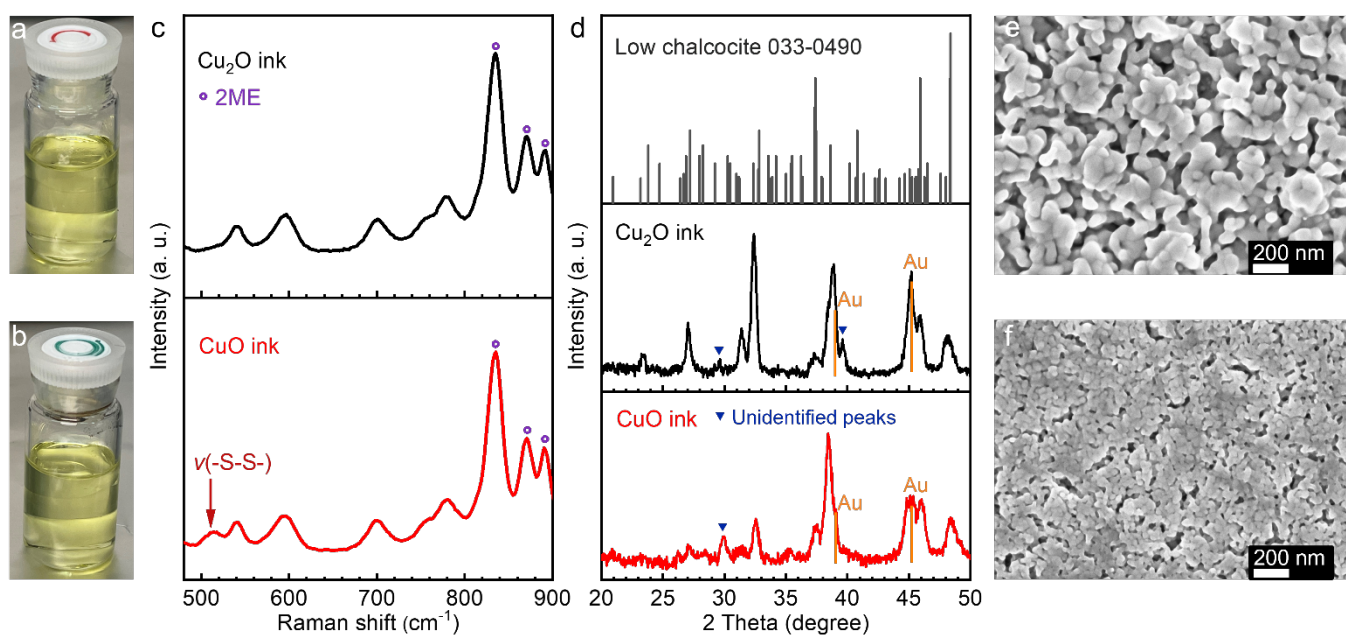
**Figure S7.** The magnitude (a, c) and imaginary part (b, d) of the Fourier transforms (FT) of Cu K-edge  $k^3$ -weighted extended X-ray absorption fine structure (EXAFS) spectra of 0.35 M CuCl ink. Green solid lines represent experimental data and black dash line represents fits based on chalcocite ( $\text{Cu}_2\text{S}$ ) and nantokite ( $\text{CuCl}$ ).<sup>1,2</sup>



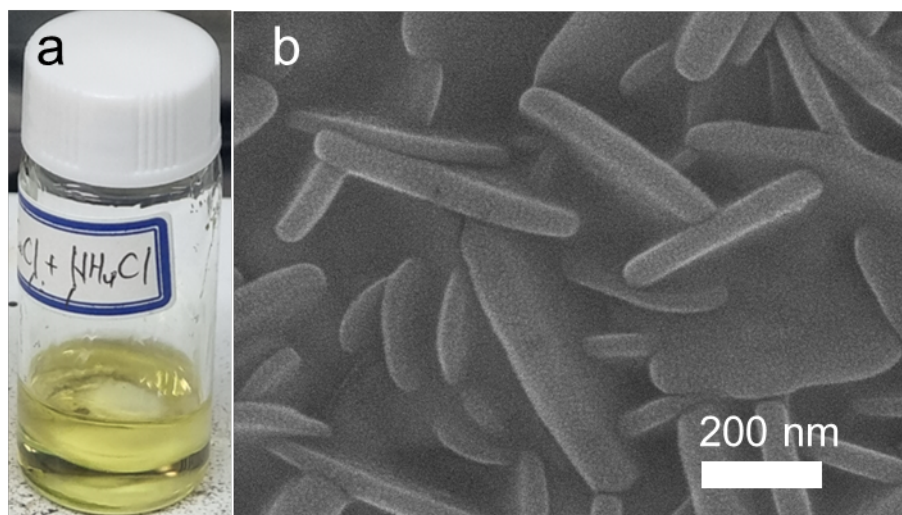
**Table S1.** Structural parameters of 0.35 M CuCl ink obtained from Cu-S fit based on chalcocite (Cu<sub>2</sub>S) and Cu-Cl fit based on nantokite (CuCl).<sup>1,2</sup>

Fit	CN	R (Å)	$\sigma^2$ (Å <sup>2</sup> )	E <sub>0</sub> (eV)
Cu-S fit	2.5 (+/- 0.4)	2.28 (+/- 0.01)	0.008 (+/- 0.002)	4.4 (+/- 1.5)
Cu-Cl fit	2.2 (+/- 0.3)	2.26 (+/- 0.01)	0.008 (+/- 0.002)	4.9 (+/- 1.3)

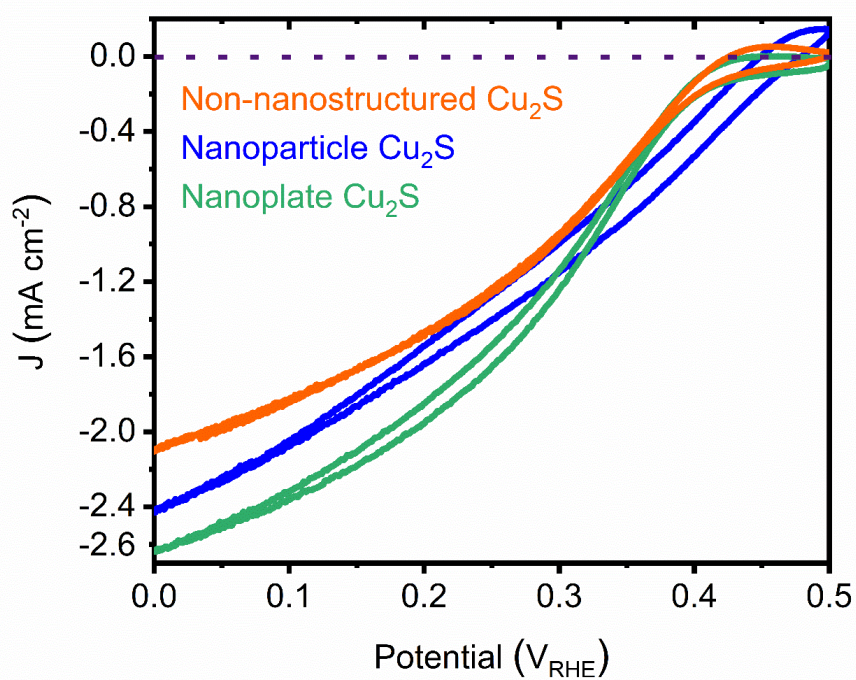
<sup>a</sup>CN: coordination number, R: interatomic distance,  $\sigma^2$ : pseudo Debye-Waller factor, E<sub>0</sub>: shift in threshold energy, S<sub>0</sub><sup>2</sup>: intrinsic loss factor fixed to 0.8 determined from fitting a Cu metal foil spectrum.



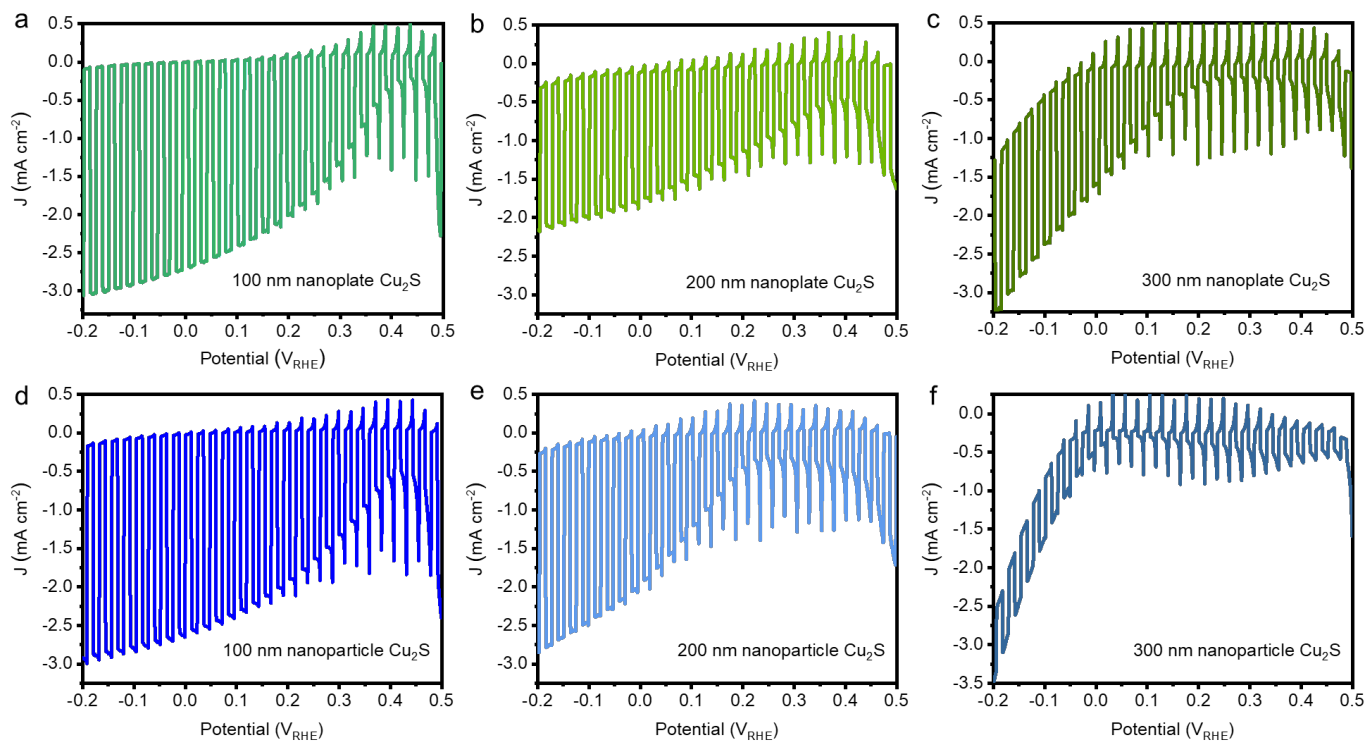
**Figure S8.** (a) Optical image of 0.175 M  $\text{Cu}_2\text{O}$  ink. (b) Optical image of 0.35 M  $\text{CuO}$  ink. (c) Molecular structure analysis of 0.175 M  $\text{Cu}_2\text{O}$  and 0.35 M  $\text{CuO}$  ink molecular inks by liquid-phase Raman spectroscopy normalized according to the 2ME peaks. (d) GIXRD patterns of thin films prepared from 0.175 M  $\text{Cu}_2\text{O}$  ink and 0.35 M  $\text{CuO}$  ink. The unidentified peaks do not match with any copper oxides or copper chlorides. (e) Plan view SEM image of the thin film prepared from the 0.175 M  $\text{Cu}_2\text{O}$  ink. (f) Plan view SEM image of the thin film prepared from the 0.35 M  $\text{CuO}$  ink.



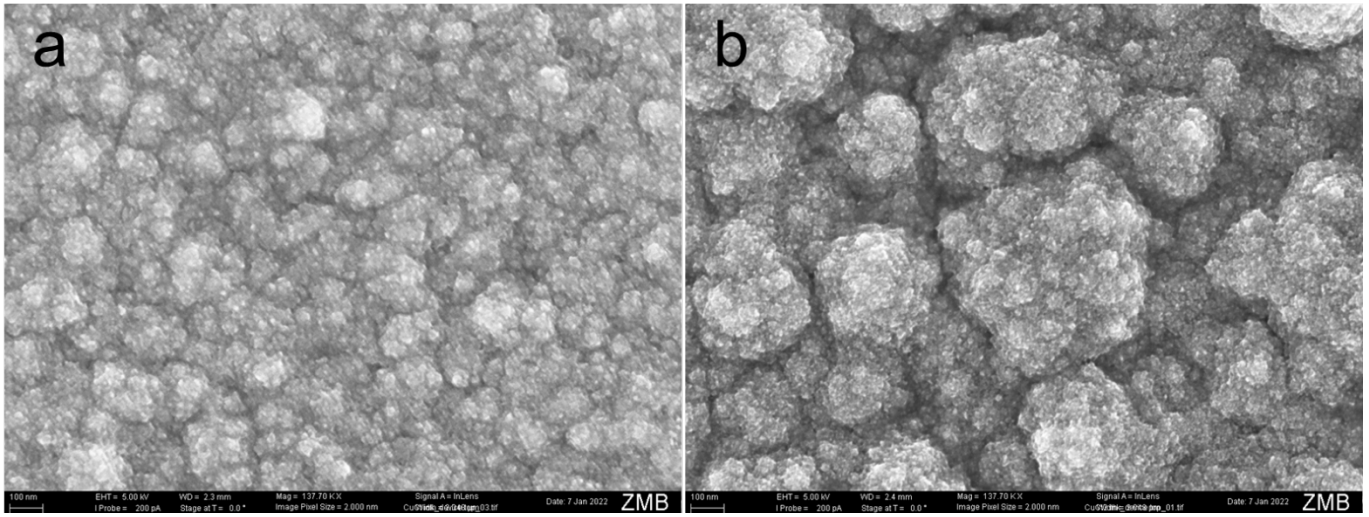
**Figure S9.** (a) Optical image of the (0.35 M CuCl+0.35 M NH<sub>4</sub>Cl) ink. (b) Plan view SEM image of the thin film prepared from the (0.35 M CuCl+0.35 M NH<sub>4</sub>Cl) ink.



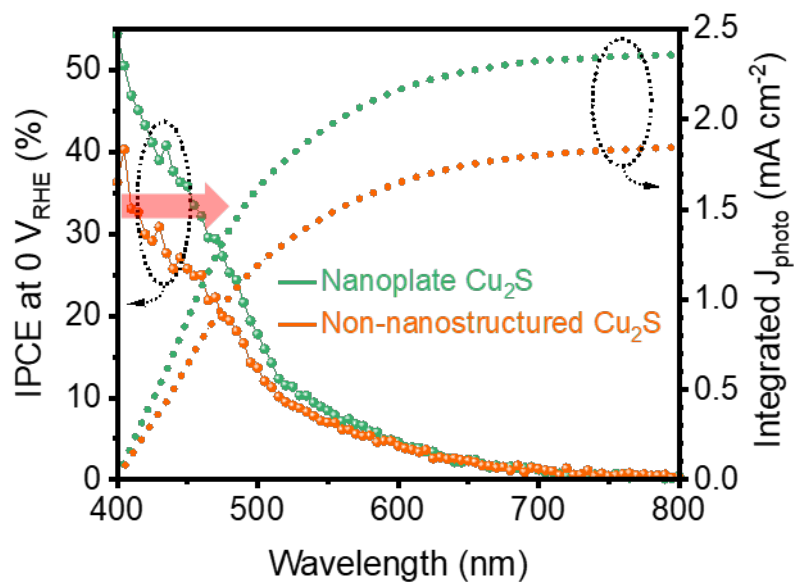
**Figure S10.** Cyclic voltammetry (CV) scans of Cu<sub>2</sub>S photocathodes prepared from nanoplate, nanoparticle, and non-nanostructured Cu<sub>2</sub>S thin films. Note: the non-nanostructured Cu<sub>2</sub>S data comes from our previous work.<sup>3</sup>



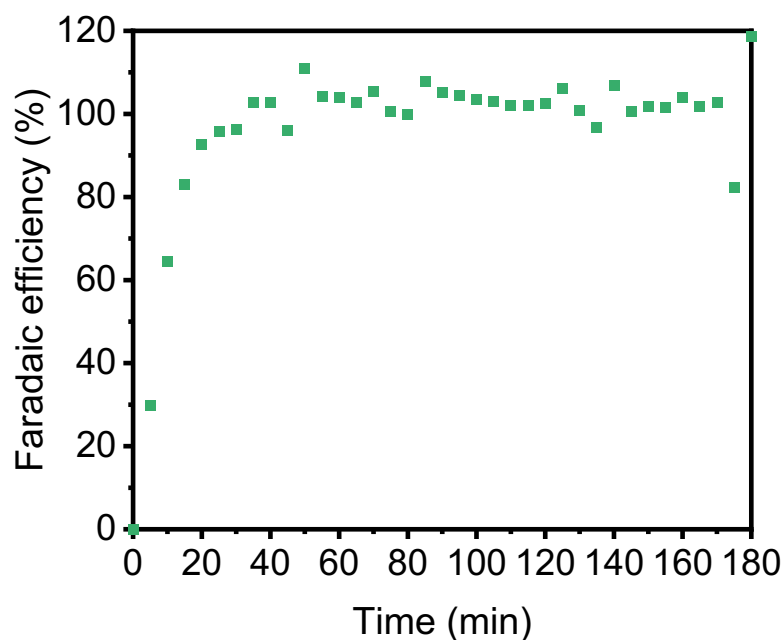
**Figure S11.** *J-E* curves of  $\text{Cu}_2\text{S}$  photocathodes based on different thickness of nanostructured  $\text{Cu}_2\text{S}$  thin films under simulated on-off AM1.5 G illumination ( $100 \text{ mW cm}^{-2}$ ).



**Figure S12.** The top-view SEM images of  $\text{Cu}_2\text{S}$  photocathodes (FTO/Au/  $\text{Cu}_2\text{S}$ /CdS/ $\text{TiO}_2$ / $\text{RuO}_x$ ) based on (a) nanoplatform  $\text{Cu}_2\text{S}$  thin film and (b) nanoparticle  $\text{Cu}_2\text{S}$  thin film.



**Figure S13.** Incident photon-to-current efficiency (IPCE) spectra of the Cu<sub>2</sub>S photocathodes at an applied bias of 0 V<sub>RHE</sub> under monochromatic illumination with 10% white light bias.



**Figure S14.** Faradaic efficiency of the  $\text{Cu}_2\text{S}$  photocathode based on the nanoplate  $\text{Cu}_2\text{S}$  thin film under constant bias at 0  $V_{\text{RHE}}$  performed in a 1.0 M phosphate buffer solution (pH 7.0) using an LED light source where the intensity was adjusted to obtain similar current densities as those obtained under simulated AM1.5 G illumination ( $100 \text{ mW cm}^{-2}$ ).

#### References:

- 1 H. T. Evans, *Nature Physical Science*, 1971, **232**, 69–70.
- 2 R. W. G. Wyckoff and E. Posnjak, *J. Am. Chem. Soc.*, 1922, **44**, 30–36.
- 3 X. Zhang, W. Yang, W. Niu, P. Adams, S. Siol, Z. Wang and S. D. Tilley, *ChemSusChem*, 2021, **14**, 3967–3974.